

ALD LAB SAXONY

Atomic layer deposition (ALD) is currently the fastest growing thin film deposition technology, boasting an annual equipment and precursor market volume in excess of USD two billion. CVD and ALD deposition techniques present diverse possibilities for accommodating the heightened interest in thin and ultrathin conformal coatings for numerous applications seen today. Over the last decade, Dresden has become a hotbed for ALD.



Advantages

- 15 years' experience,
- Close collaboration with industry
- Broad program covering all technologies
- Sampling and pilot capability
- Transfer to production

The strategic coordinator, Dr. Bianca Milde, will be representing ALD LAB SAXONY in the Cool Silicon Cluster business delegation that will visit Toronto and Ottawa from October 23-27, 2017.

If you are interested in discussing potential business opportunities with ALD LAB SAXONY, please contact:



**Canadian German Chamber of Industry
and Commerce Inc.**

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